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BIB DATA SHEET

CONFIRMATION NO. 8166

10/587,427 07/26/2006 438 1792 Serie 6497 RULE APPLICANTS Eri Tsukada, Ibaraki, JAPAN; Christian Dussarrat, Ibaraki, JAPAN; Jean-Marc Girard, Paris, FRANCE; ** CONTINUING DATA **********************************	SERIAL NUM	RIAL NUMBER FILING				CLASS	GROUP ART UN				
APPLICANTS Eri Tsukada, Ibaraki, JAPAN; Christian Dussarrat, Ibaraki, JAPAN; Jean-Marc Girard, Paris, FRANCE; ****CONTINUING DATA ******** This application is a 371 of PCT/IB05/00170 01/19/2005 ***FOREIGN APPLICATIONS ***** JAPAN 2004-025479 02/02/2004 *** IF REQUIRED, FOREIGN FILING LICENSE GRANTED *** 04/04/2007 Foreign Priority claimed	10/587,42					438	1792			NO. Serie 6497	
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*** FOREIGN APPLICATIONS ************************************											
FILING FEE RECEIVED 900 Foreign Priority claimed	** FOREIGN APPLICATIONS ************************************										
35 USC 119(a-d) conditions met 2 Yes No Verified and Acknowledged // Examiner's Signature											
ADDRESS AIR LIQUIDE Intellectual Property 2700 POST OAK BOULEVARD, SUITE 1800 HOUSTON, TX 77056 UNITED STATES TITLE Method for producing silicon nitride films and silicon oxynitride films by chemical vapor deposition FEES: Authority has been given in Paper No to charge/credit DEPOSIT ACCOUNT No for following: JAPAN 1 10 2 Allowance JAPAN 1 10 2 Allowance JAPAN 1 10 2	j ,			☐ Met after						1	
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